

Title (en)

GRAVURE PRINTING MACHINE AND METHOD FOR APPLYING AT LEAST ONE PRINTING FLUID ONTO AT LEAST ONE SUBSTRATE

Title (de)

INTAGLIO-TIEFDRUCKMASCHINE UND VERFAHREN ZUM AUFBRINGEN VON ZUMINDEST EINEM DRUCKFLUID AUF ZUMINDEST EIN SUBSTRAT

Title (fr)

MACHINE D'IMPRESSION EN CREUX ET PROCÉDÉ D'APPLICATION D'AU MOINS UN FLUIDE D'IMPRESSION SUR AU MOINS UN SUBSTRAT

Publication

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Application

**EP 20797457 A 20201026**

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Abstract (en)

[origin: WO2021139910A1] The invention relates to a gravure printing machine comprising at least one gravure printing unit that has at least one gravure cylinder (03) and at least one impression cylinder (01), wherein at least one inking system (18) and/or at least one ink collecting cylinder (12) is arranged on the at least one gravure cylinder (03), wherein the gravure printing machine comprises at least one printing head (04), which is arranged on the at least one gravure cylinder (03) or on the at least one impression cylinder (01). The invention further relates to a method for applying at least one printing fluid onto at least one substrate (10).

IPC 8 full level

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